

Shee: 1 of 1

U.S. Department of Commerce, Patent and Trademark Office				Application No.: 09/578,798								
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)				Filing Date: May 23, 2000								
				First Named Inventor: Jaime Poiris								
				Group Art Unit: 2873								
				Examiner Name: William C. Choi								
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U.S. Patent Documents												
*Examiner Initial		Document Number	Date	Name	Class	Filing Date If Appropriate						
W.C.	3.	5,348,002	9/20/94	Caro	128	633						
W.C.	4.	5,555,471	Sep/10/96	Xu et al.	356	357						
W.C.	5.	5,914,782	Jun/22/99	Sugiyama	356	351						
W.C.	6.	6,392,752	5/21/02	Johnson	356	511						
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)												
W.C.	7	Stine, B. et al., "Rapid Characterization and Modeling of Pattern-Dependent Variation in Chemical-Mechanical Polishing", IEEE Transactions on Semiconductor Manufacturing, Vol. 11, No. 1, pp. 129-140 (Feb. 1998)										
Examiner <i>WCC</i>		Date Considered <i>10/7/03</i>										
*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.												

